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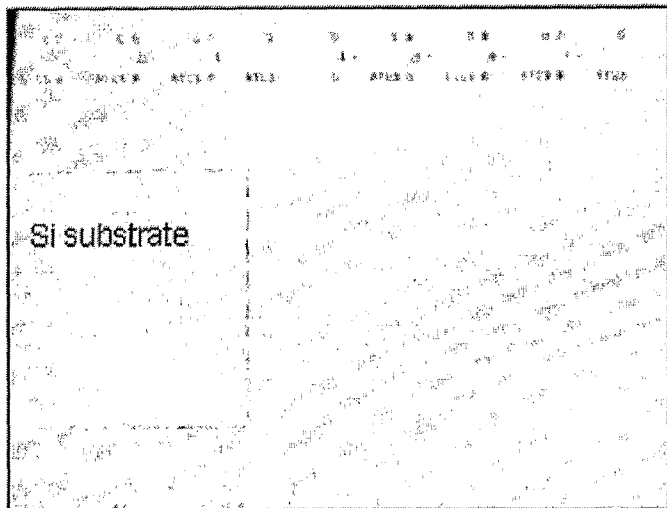
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(54) Title: COMPOSITION USEFUL FOR REMOVAL OF BOTTOM ANTI-REFLECTION COATINGS FROM PATTERNED ION-IMPLANTED PHOTORESIST WAFERS



(57) Abstract: A method and composition for removing a bottom anti-reflection coating (BARC) layer from semiconductor substrates having such BARC layers is described. The removal composition includes a supercritical fluid, a co-solvent, an etchant and a surfactant. Such removal compositions overcome the intrinsic deficiency of SCCO_2 as a removal reagent, viz., the non-polar character of SCCO_2 and its associated inability to solubilize species such as inorganic salts and polar organic compounds that must be removed from the semiconductor substrate.

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